

# *ULTRA-LOW DISORDER GRAPHENE QUANTUM DOT-BASED SPIN QUBITS FOR CYBER SECURE FOSSIL ENERGY INFRASTRUCTURE*

Project # DE-FE0031908

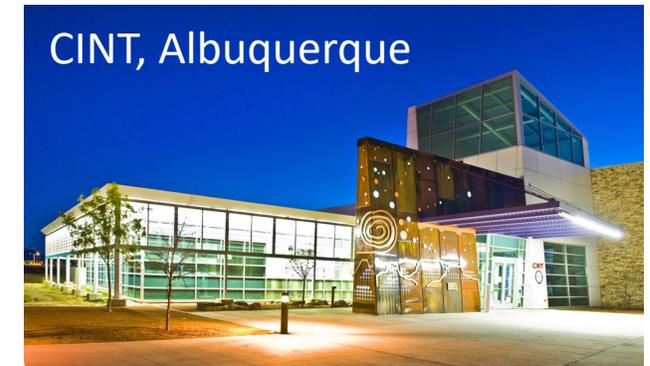
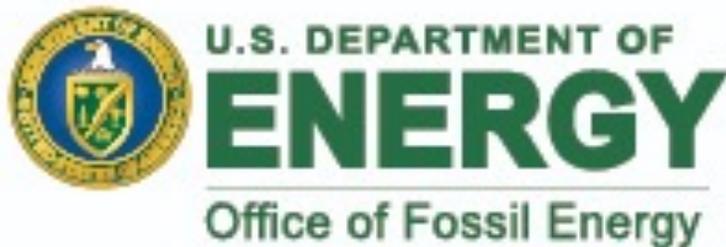
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Ramana Chintalapalle (co-PI) Venkata Surya N. Chava (co-PI)

The University of Texas at El Paso

# Acknowledgments

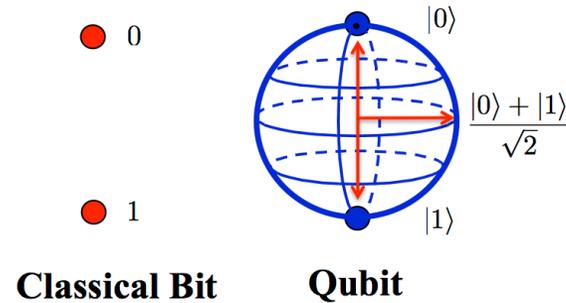
- Dr. Adam Payne (Project Manager, DOE)
- Aruna Nair, Functional Quantum Materials Laboratory (FQML), UTEP
- Center for Integrated Nanotechnologies (CINT), Albuquerque, NM
- Prof. Trevor Thornton, Director - ASU Nanofab



# Technical Background & Motivation



# Quantum Information Processing (QIP) and Quantum bits (qubits)



<https://www.bbvaopenmind.com/en/technology/digital-world/towards-the-quantum-computer-qubits-and-qudits/>



<https://physicsworld.com/a/quantum-communications-boosted-by-solid-memory-devices/>

## Physical Implementation of Qubits

- Atoms, ions, molecules
- Electronic and nuclear magnetic moments
- Charges in semiconductor quantum dots
- Charges and fluxes in superconducting circuits
- **Spin**

*Nature Physics*, 3(3), 192-196 (2007)

## DiVincenzo criteria

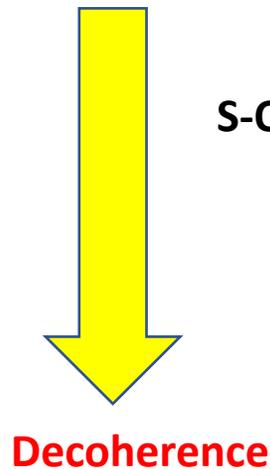
1. Long coherence time
2. Efficient initialization
3. Scalable
4. Readout
5. Universal quantum gates

*Progress of Physics*, 48(9-11), 771-783. (2000)

# GQDs for Spin Qubits

Coherence time depends on spin-orbit and hyperfine interactions in the material

III	IV	V	VI
5 B 10 (3) 20% 11 (3/2) 80%	6 C 12 (0) 99% 13 (1/2) 1%	7 N 14 (1) 99.6% 15 (1/2) 0.4%	8 O 16 (0) 99.76% 17 (5/2) 0.04% 18 (0) 0.20%
13 Al 27 (5/2) 100%	14 Si 28 (0) 92% 29 (1/2) 5% 30 (0) 3%	15 P 31 (1/2) 100%	16 S 32 (0) 95% 33 (3/2) 1% 34 (0) 4%
31 Ga 69 (3/2) 60% 71 (3/2) 40%	32 Ge 72 (0) 27% 73 (9/2) 8% 74 (0) 36%	33 As 75 (3/2) 100%	34 Se 77 (1/2) 8% 78 (0) 24% 80 (0) 50% 82 (0) 9%
49 In 113 (9/2) 5% 115 (9/2) 95%	50 Sn 118 (0) 24% 119 (1/2) 9% 120 (0) 33%	51 Sb 121 (5/2) 57% 123 (7/2) 43%	52 Te 125 (1/2) 7% 126 (0) 19% 128 (0) 32% 130 (0) 34%

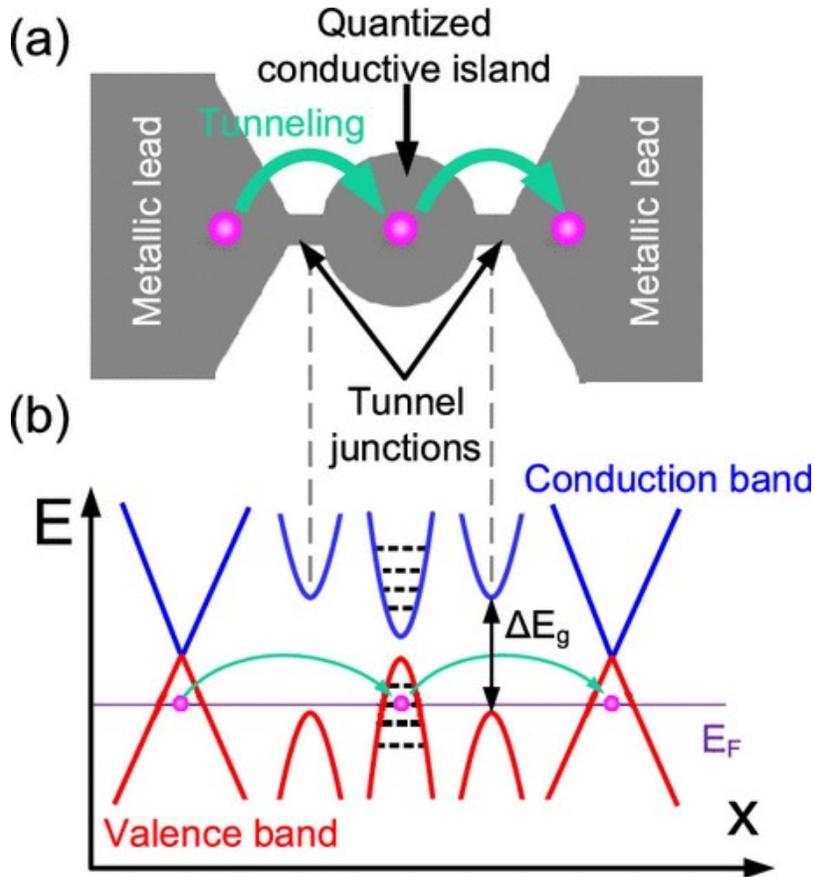


## Advantages of Graphene

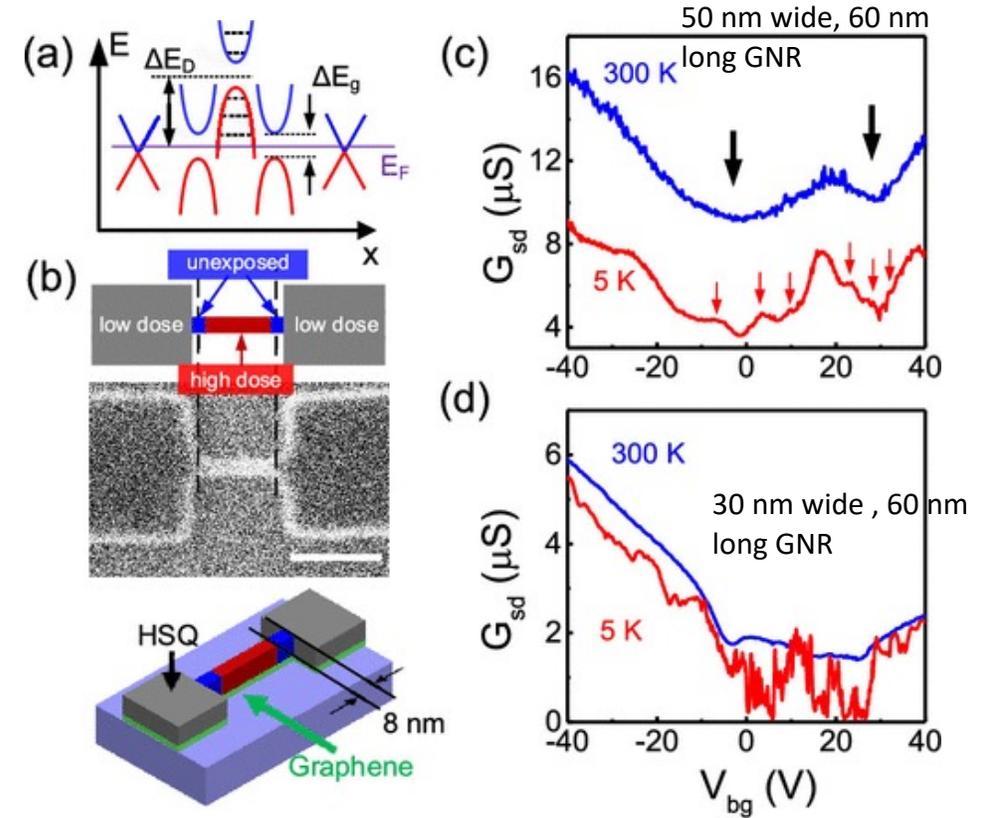
1. Very low nuclear spin
2. Weak spin-orbit coupling
3. Scalable material platform

*Nature Physics* 3.3 (2007): 192-196.

# Quantum Dots in “Graphene”



- Fabrication residues
- Substrate defects
- Edge effects (disorder)



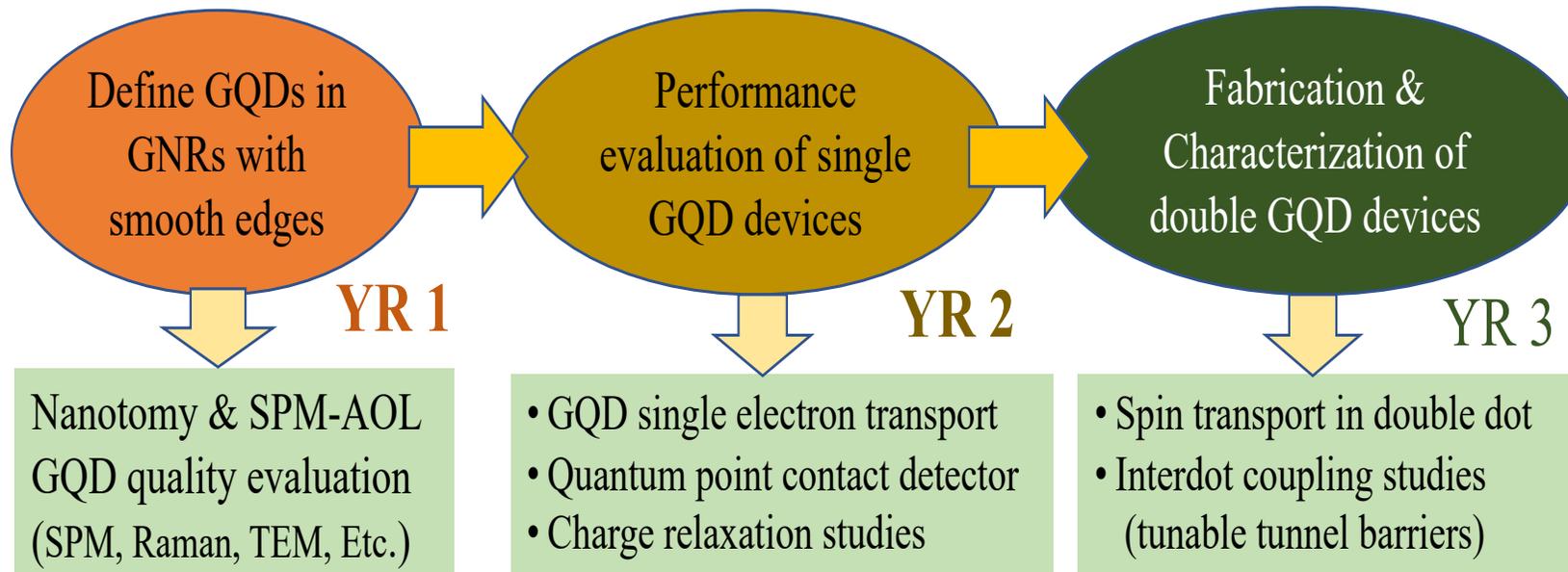
ACS nano 13.7 (2019): 7502-7507.

# Project Objectives

**Objective 1:** Define GQDs on GNR with ultralow local defects

**Objective 2:** Low-temperature characterization of quantum transport and spin relaxation times in GQDs

**Objective 3:** Develop double GQD-based qubit platform and characterize coupling effects



Outline of the overall effort of the proposed project

# PROJECT SCHEDULE

PROJECT SCHEDULE													
		Yr1				Yr2				Yr3			
S. No.	Task Title	1	2	3	4	1	2	3	4	1	2	3	4
1	Project Management and Planning	φ											
2	Preparation of GNRs with prescribed width and smooth edges		φ		φ								
3	Device fabrication and characterization of a single-electron transistor					φ	φ		φ				
4	Characterization of GQD charge stability and charge relaxation							φ		φ	φ		
5	Fabrication and Characterization of double GQD spin qubit system												φ
6	Final Verification												φΔ
	<b>φ-Milestones</b>	<b>Δ-Go/No-Go Decision points</b>											



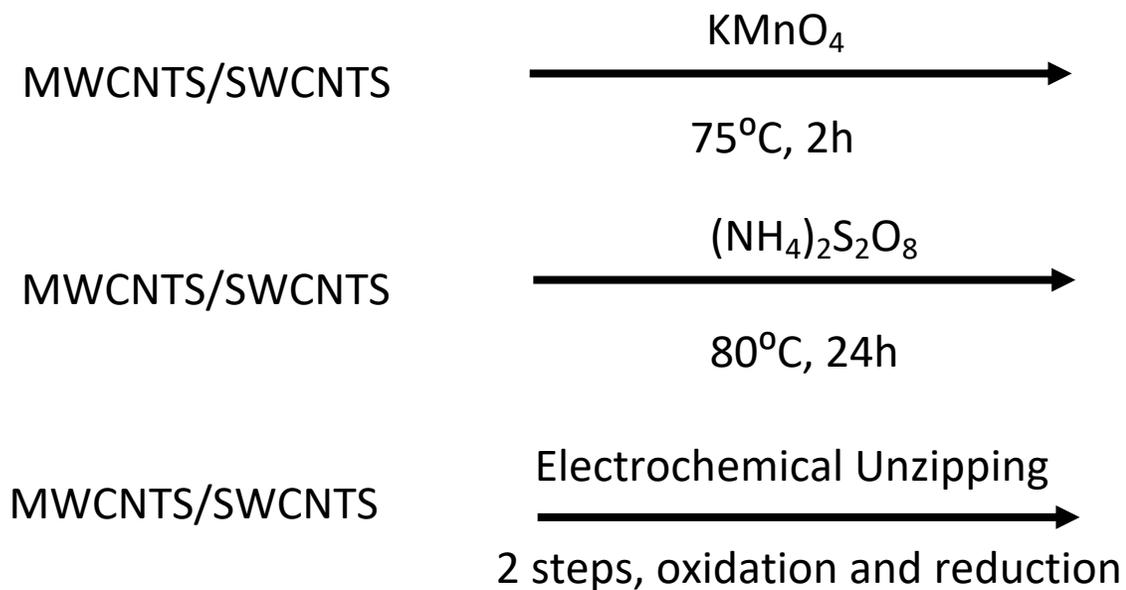
# CURRENT PROGRESS AND RESULTS



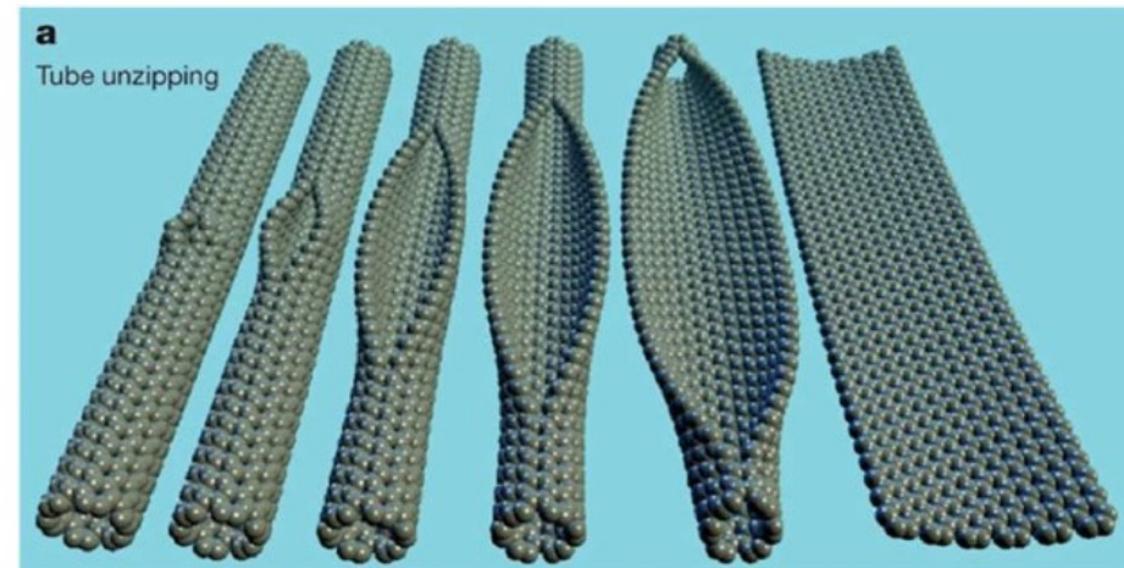
# Preparation of GNRs: Part-I

## Chemically unzipped CNTs: Material Synthesis and Characterization

- Unzipping of CNTs produces semiconducting GNRs



Unzipping of Carbon Nanotubes (CNTs)



James, Dustin K., and James M. Tour, *Macromolecular Chemistry and Physics*, 213(10-11), 1033-1050

Kosynkin, D., et. al, *Nature* 458, 872–876 (2009)

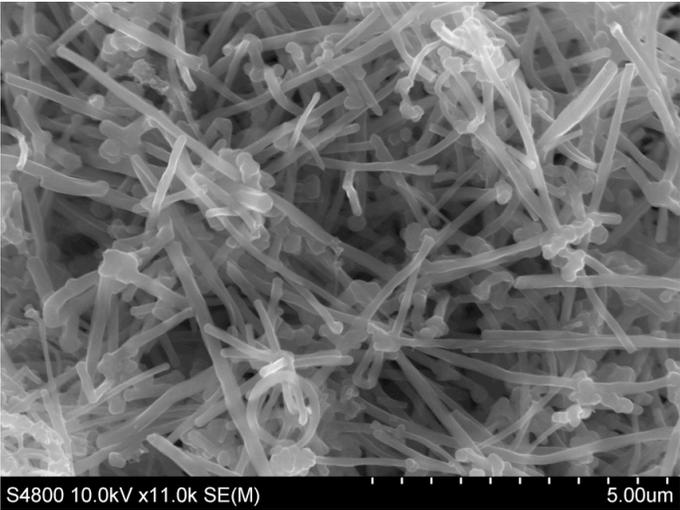
Tuo Wang, et. al, *Carbon*, 158, 2020, 615-623,

Dhanraj B. Shinde, et. al., *Journal of the American Chemical Society* 2011 133 (12), 4168-4171

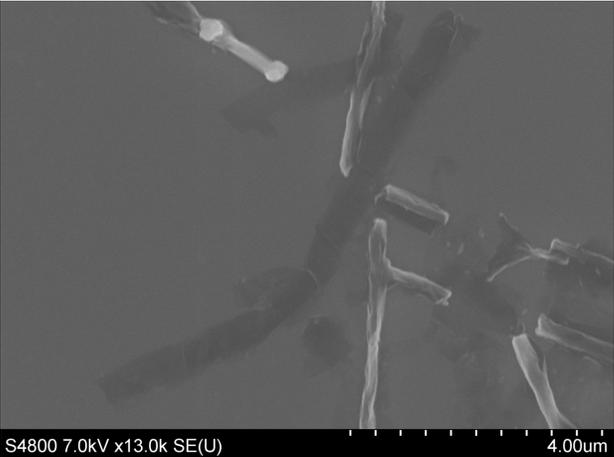
# Scanning Electron Microscopy (SEM) Results

## Unzipped MWCNTs

Pristine MWCNT



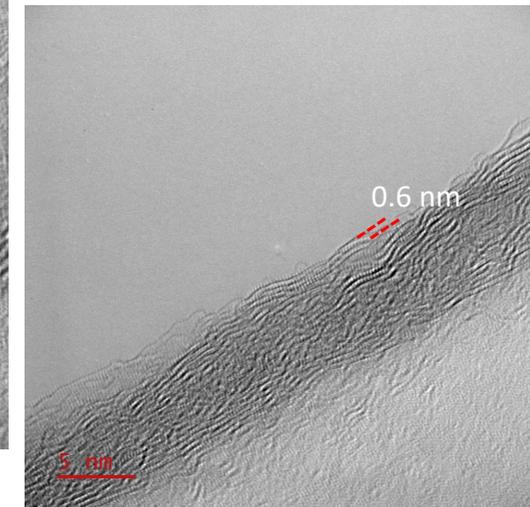
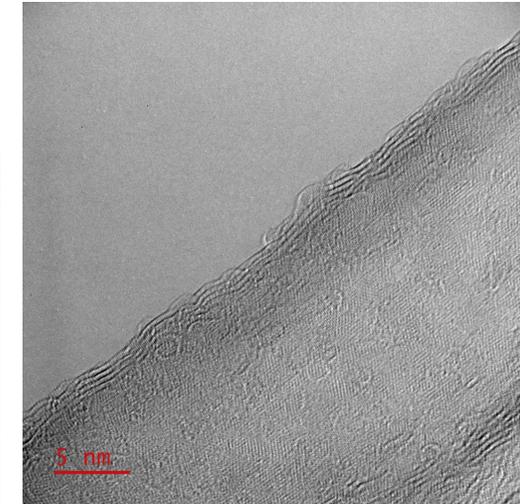
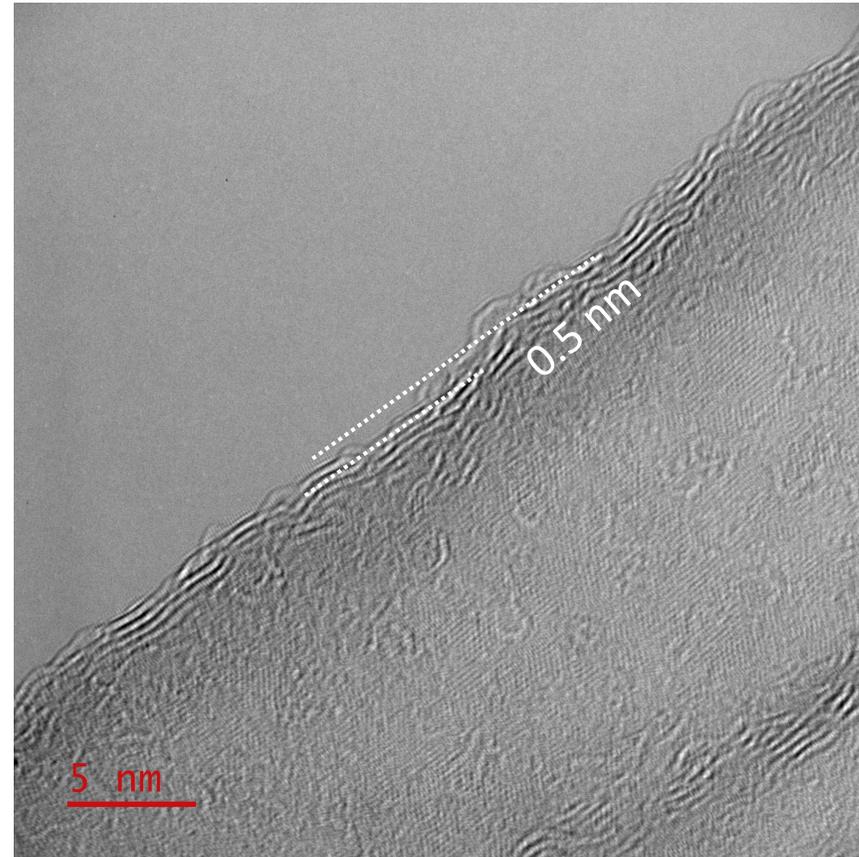
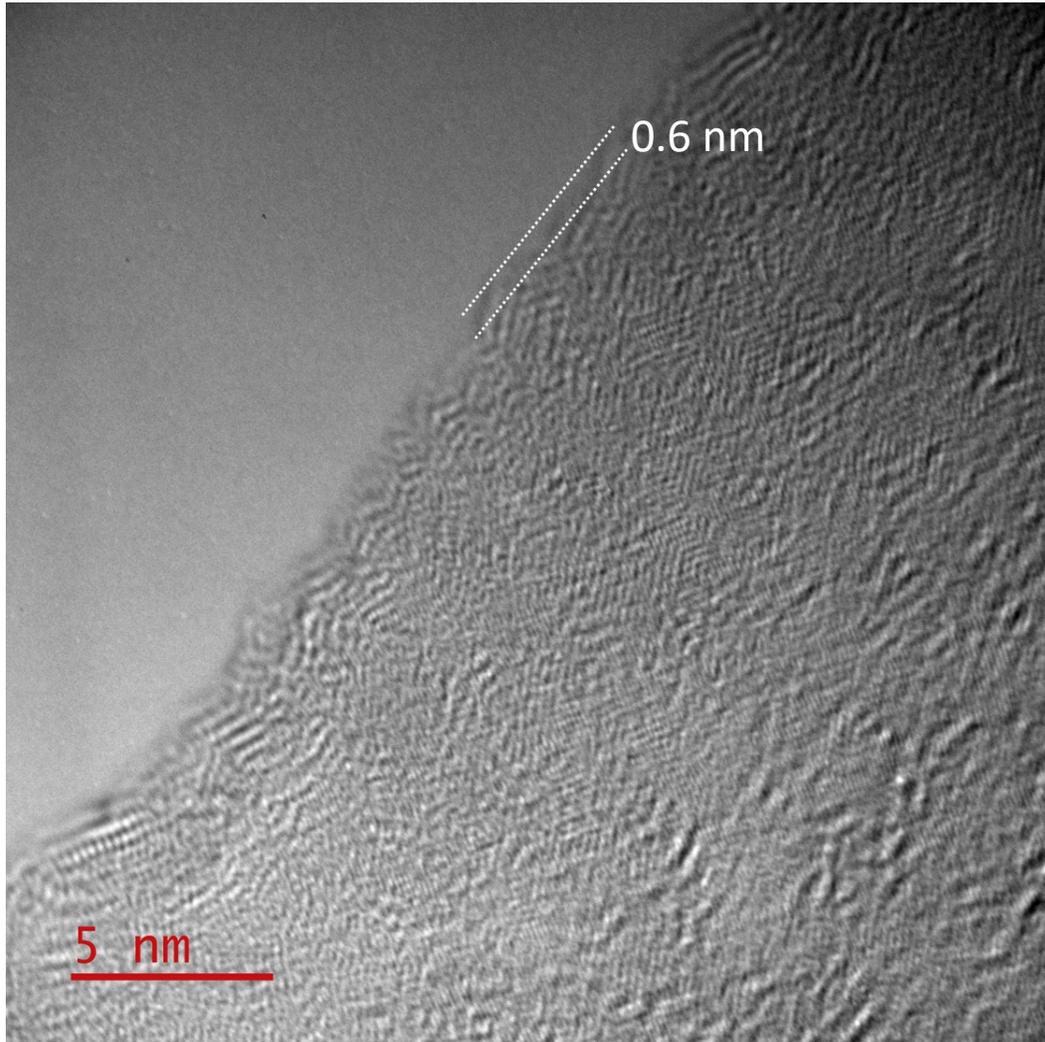
KMnO<sub>4</sub>



Ammonium persulfate

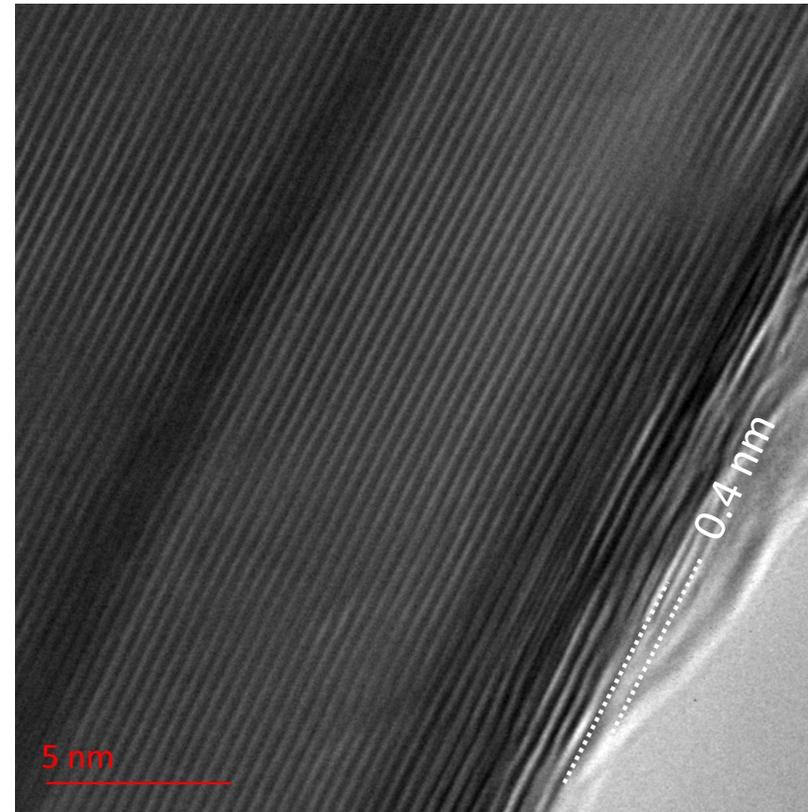
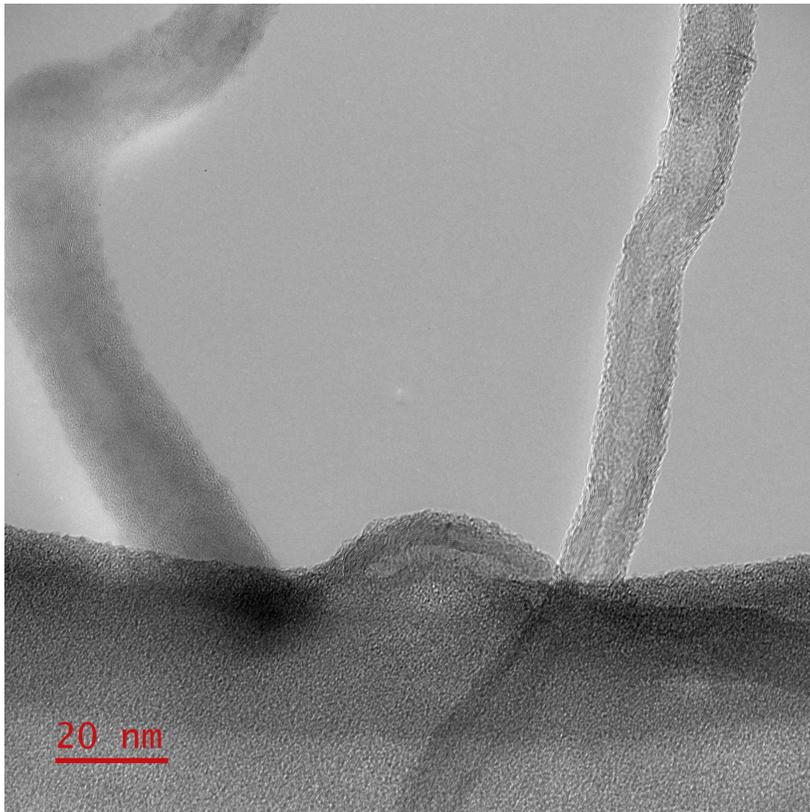


# Transmission Electron Microscopy (TEM) Results

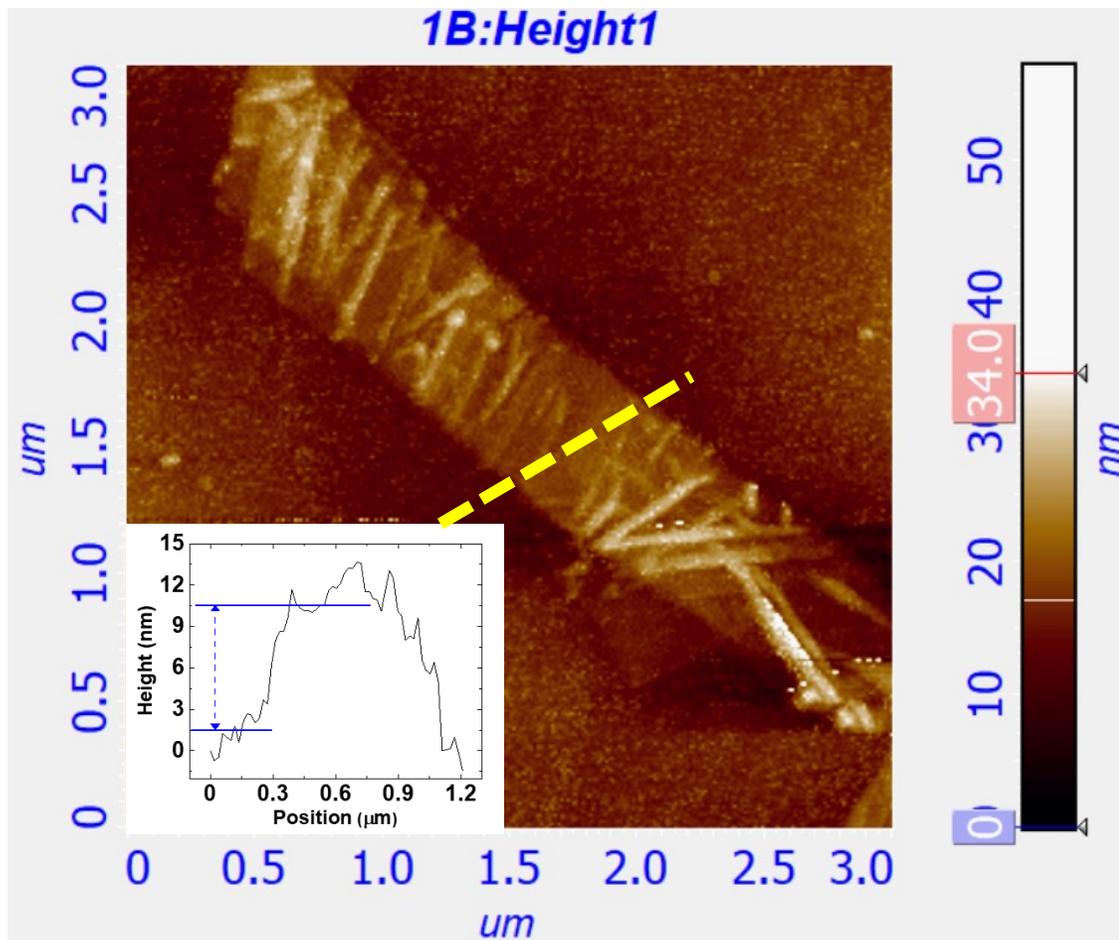


# Transmission Electron Microscopy (TEM) Results

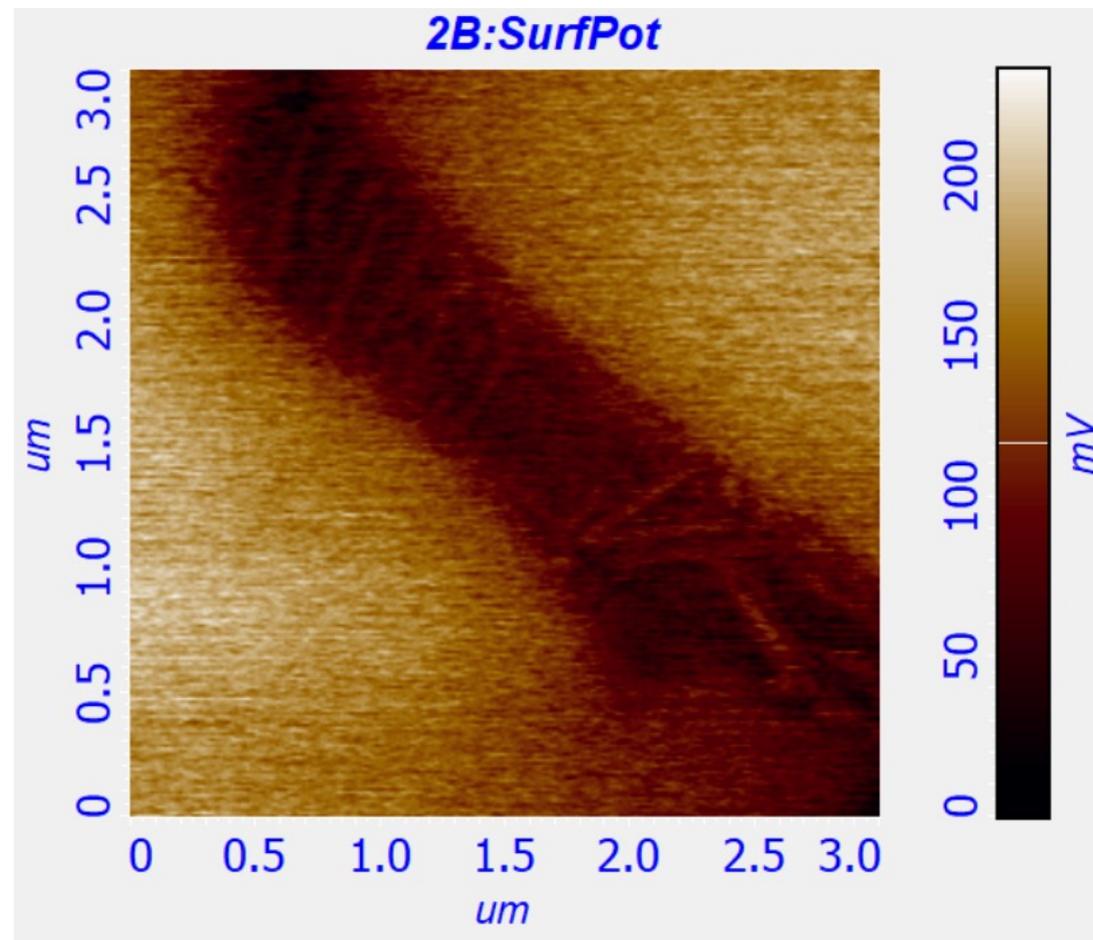
## (C) UMWCNT - $(\text{NH}_4)_2\text{S}_2\text{O}_8$



# Topography

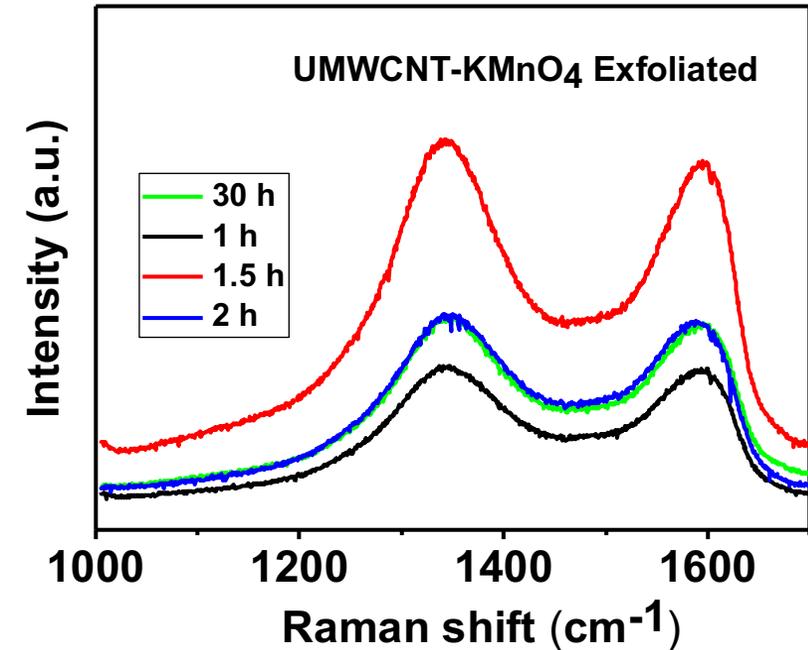
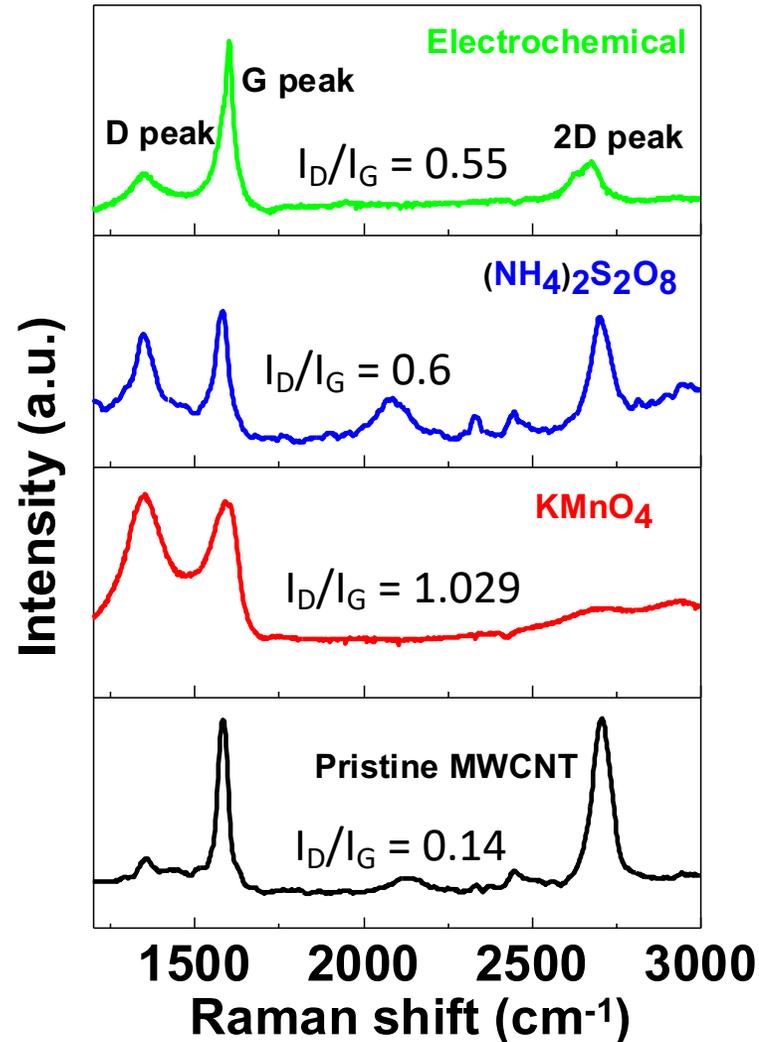


# Surface Potential

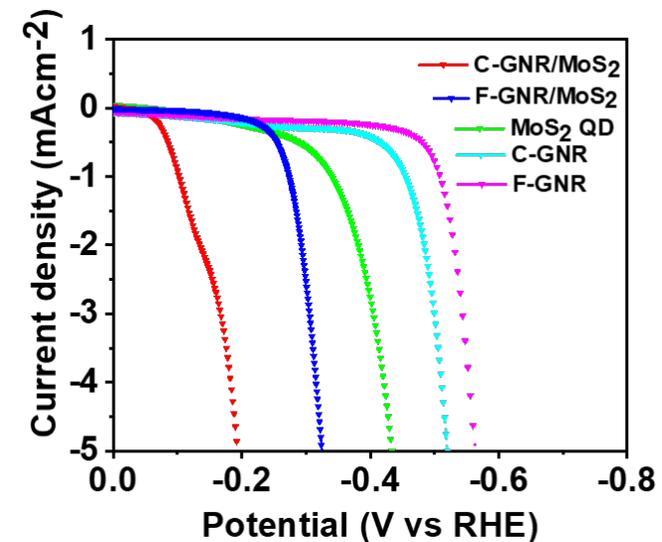
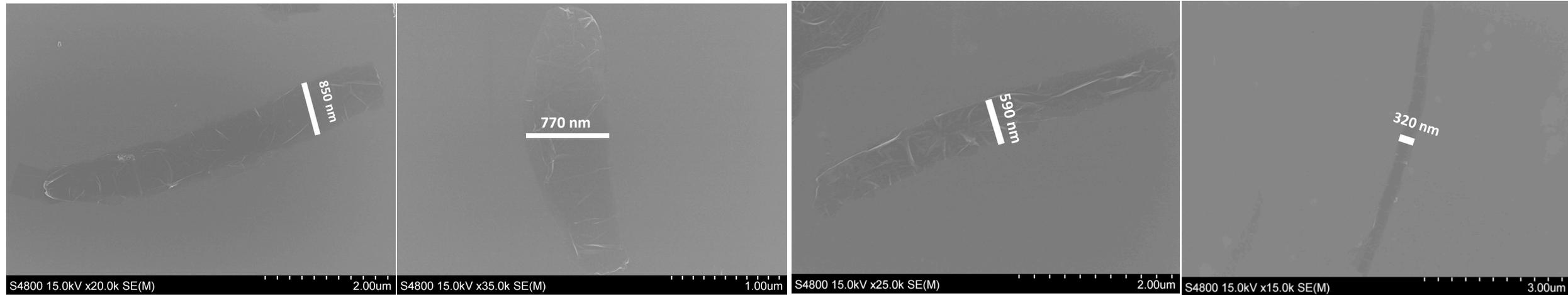


# Raman spectroscopic investigation of unzipped MWCNTs

- ❑ Existence of D band is an indication of the defects present
- ❑  $I_D/I_G$  values are used to compare the amount of defects
- ❑ Unzipping using  $(\text{NH}_4)_2\text{SO}_4$  appears to produce less defects compared to  $\text{KMnO}_4$



# Part-I: Outcome



1. “Platinum-like Hydrogen Evolution Reaction Onset for GNR/MoS<sub>2</sub> Heterostructure through curvature-dependent Electron Density Modulation and Enhanced Interfacial Charge Transfer”, Aruna N. Nair, Mohamed F Sanad, Venkata S.N. Chava, and Sreeprasad T. Sreenivasan, (Submitted).
2. “Graphene Nanoribbon-Fullerene (GNR-C<sub>60</sub>) Heterostructure for Nitrogen Reduction Reaction”, Aruna N. Nair and Sreeprasad T. Sreenivasan, 240<sup>th</sup> Electrochemical Society (ECS) Meeting, Oct 10-14, 2021

## PROJECT SCHEDULE

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3	Device fabrication and characterization of a single-electron transistor					φ	φ		φ				
4	Characterization of GQD charge stability and charge relaxation							φ		φ	φ		
5	Fabrication and Characterization of double GQD spin qubit system												φ
6	Final Verification												φΔ
	<b>φ-Milestones</b>	<b>Δ-Go/No-Go Decision points</b>											



# Preparation of GNRs: Part-2

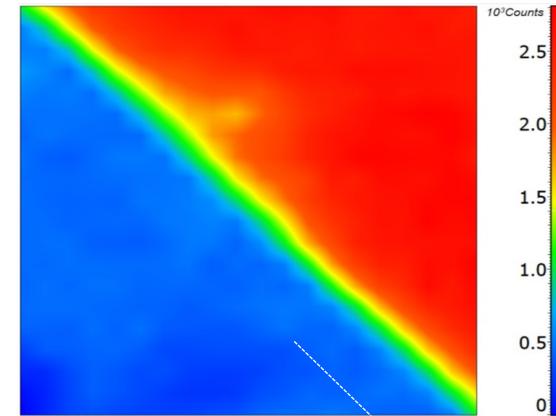
## CVD graphene synthesis and material characterization



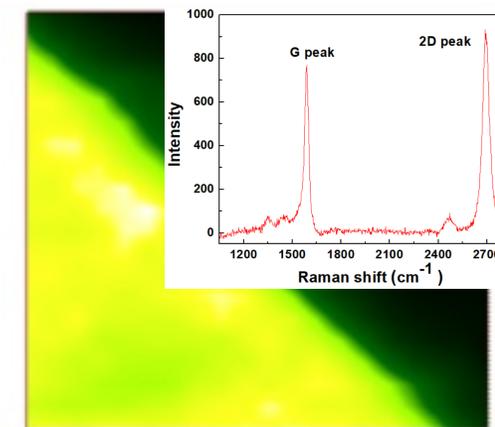
Two zone CVD furnace



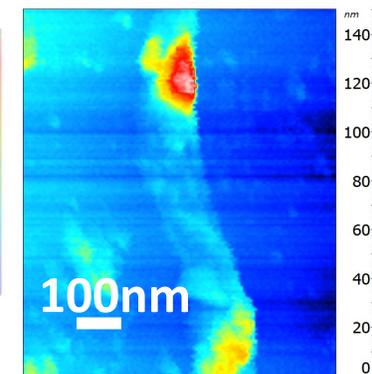
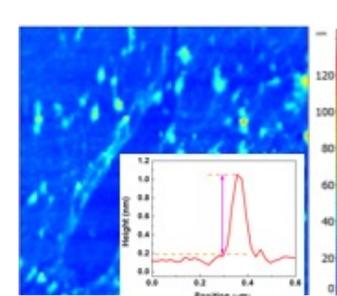
Integrated setup for SPM and Raman characterization



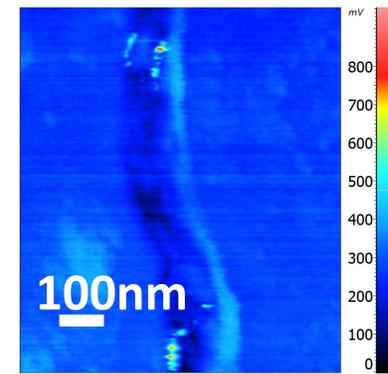
Raman spectrum 2D map



G peak

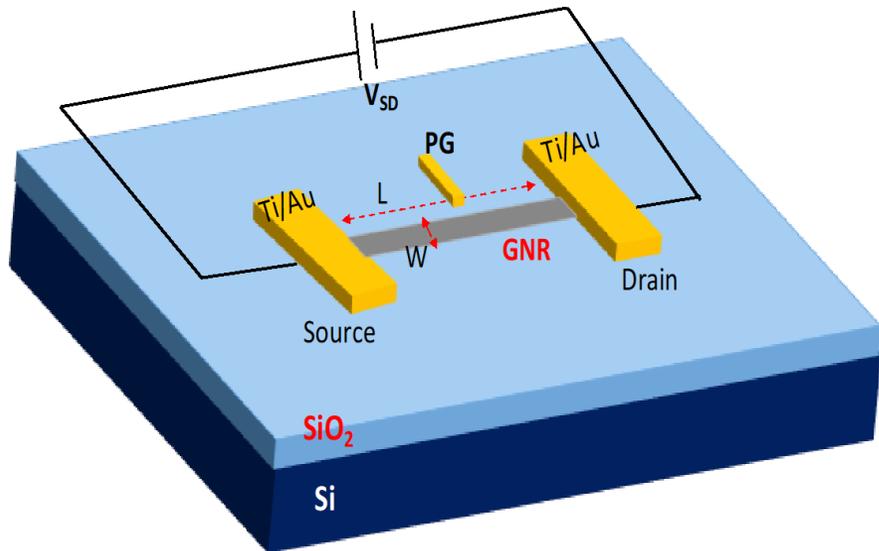


2D Height map



2D KPFM map

# Electron beam lithography (EBL) for CVD graphene patterning into GNRs

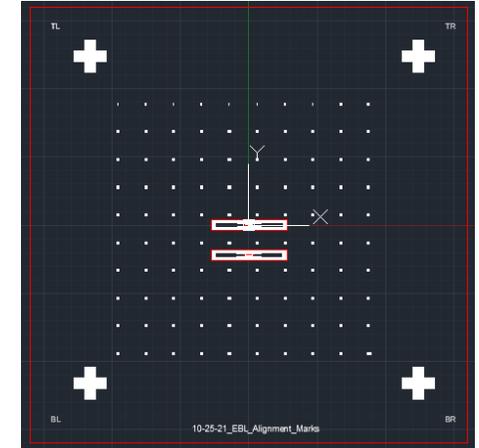


**GNR FET device**

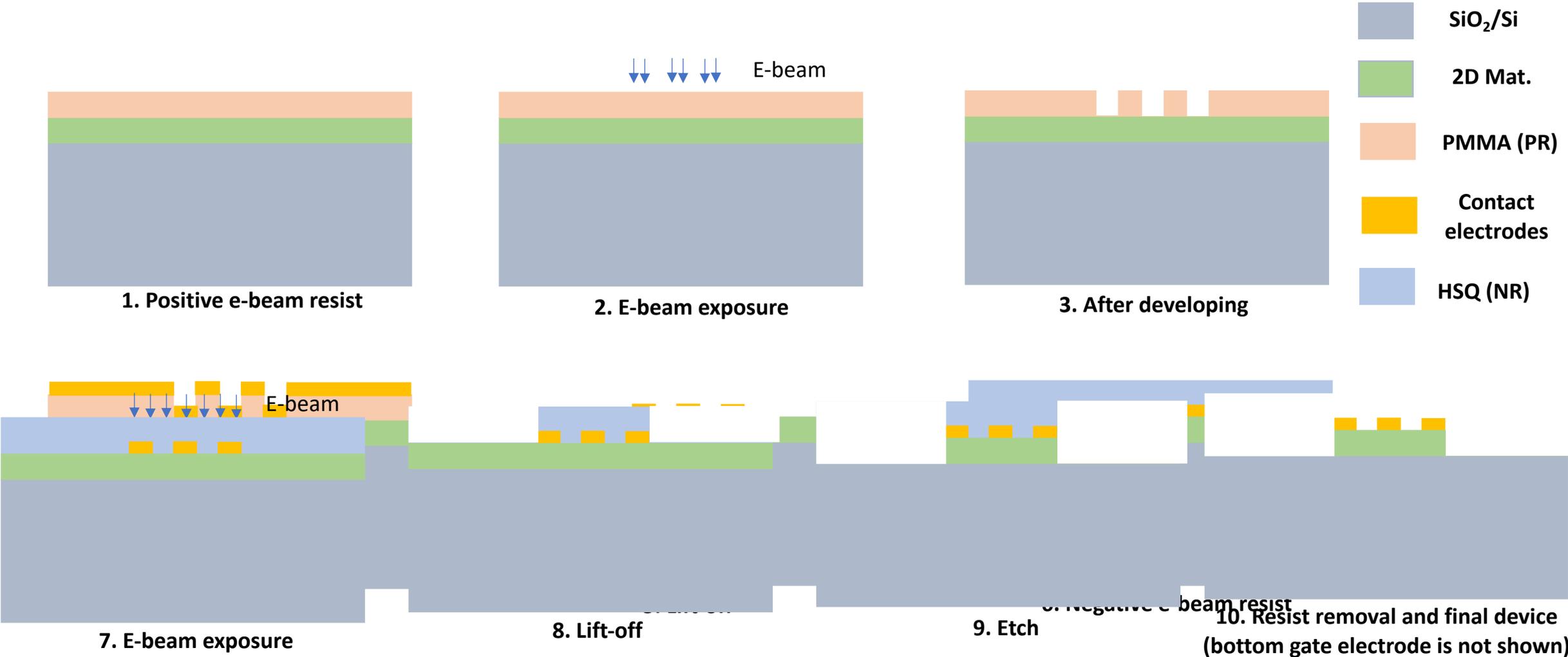
## Process flow

1. Substrate with graphene
2. Design mask-file (CAD)
3. Prepare (coat) substrate for photo/e-beam lithography
4. Expose PR under UV light/e-beam
5. Develop
6. Optical inspection

## Mask layout



# GNR Device Fabrication Process Flow



# GNR FET Device Fabrication Process Details

- Starting substrates will require metal alignment keys for EBL alignment and for reference to 2D material location
- The SEM will be used to identify 2D particle location for probe pattern placement with reference to alignment keys

*Step 1.* Coat PMMA positive EBL resist – PMMA 950 A6

*Step 2.* Exposure on EBL – Align to keys and expose probe pattern in PMMA, (Exposure dose  $\sim 600\text{uC}/\text{cm}^2$ )

*Step 3.* Develop PMMA resist using MIBK:IPA

*Step 4.* Deposit Cr/Au metal for probe pattern lift-off

*Step 5.* Lift-off metal/resist using acetone

*Step 6.* Coat negative resist – maN-2403

*Step 7.* Exposure on EBL – Align to keys, expose pattern in maN-2403 to protect probed graphene (Exp  $\sim 250\text{uC}/\text{cm}^2$ )

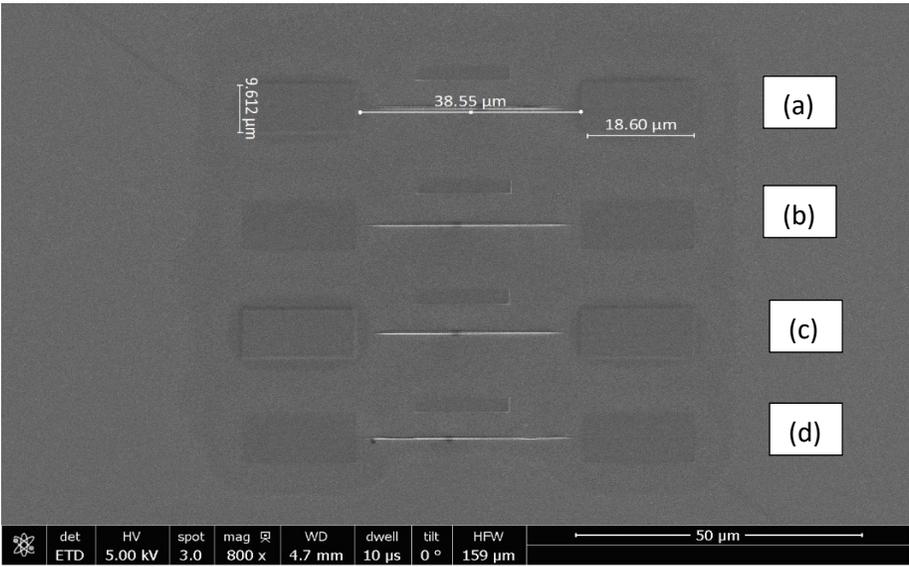
*Step 8.* Develop maN-2403 resist

*Step 9.* Etch excess graphene (RIE)

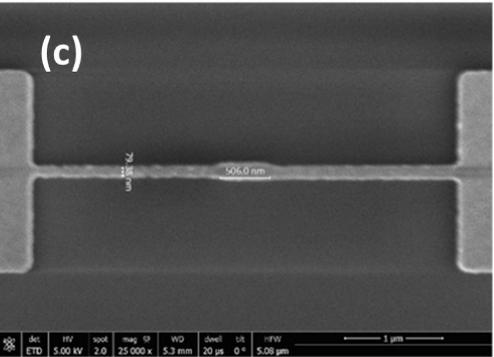
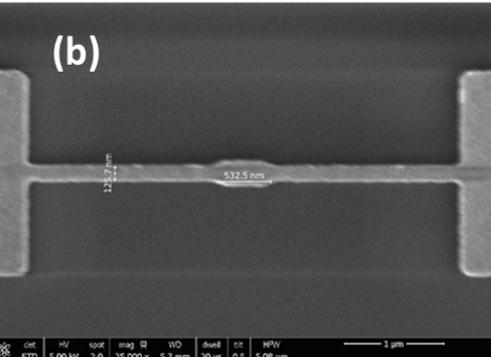
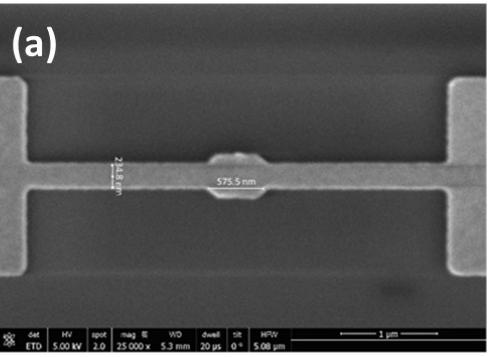
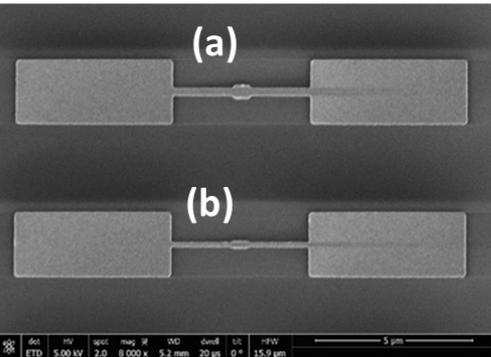
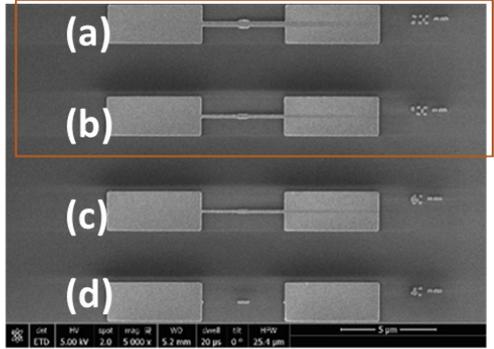
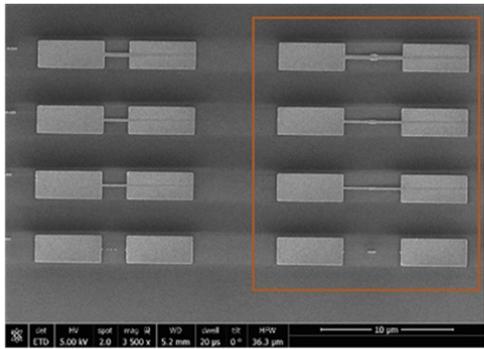
*Step 10.* Strip resist and coat backside metal



# SEM images: Electron beam lithography (EBL) patterning of graphene into GNRs



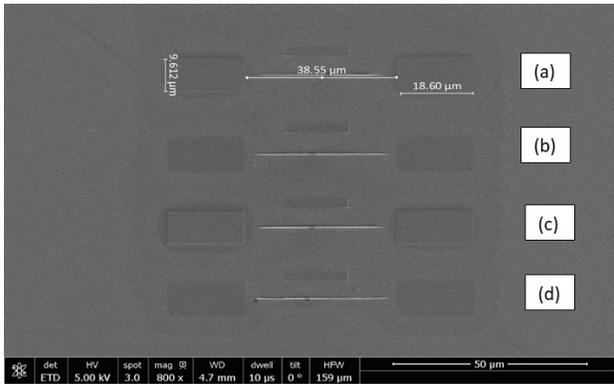
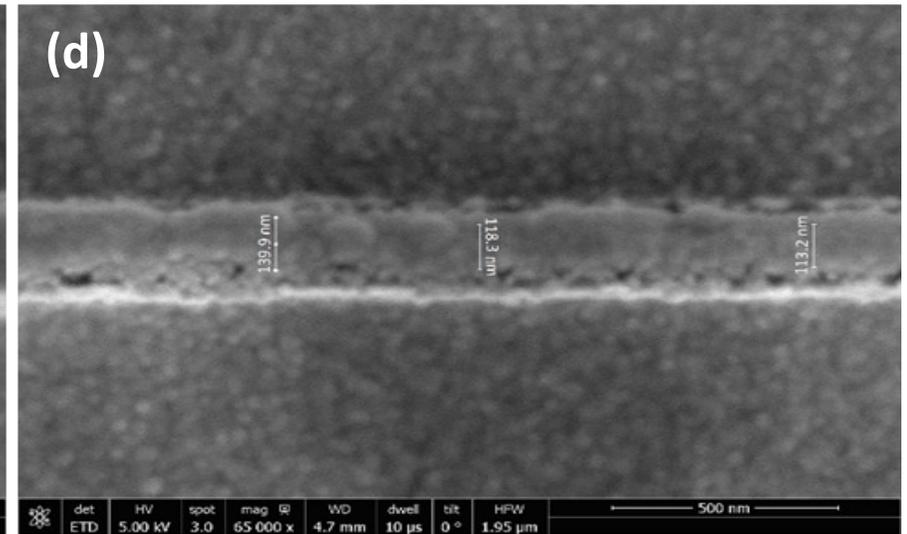
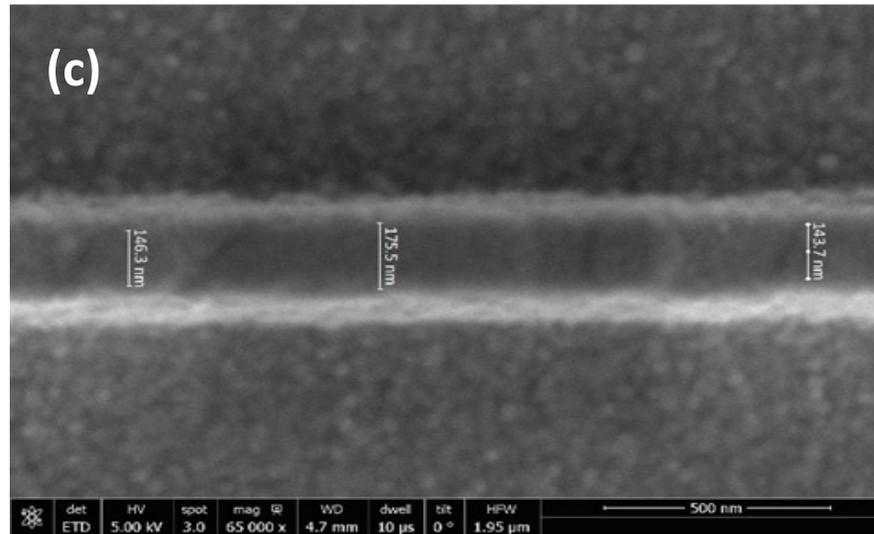
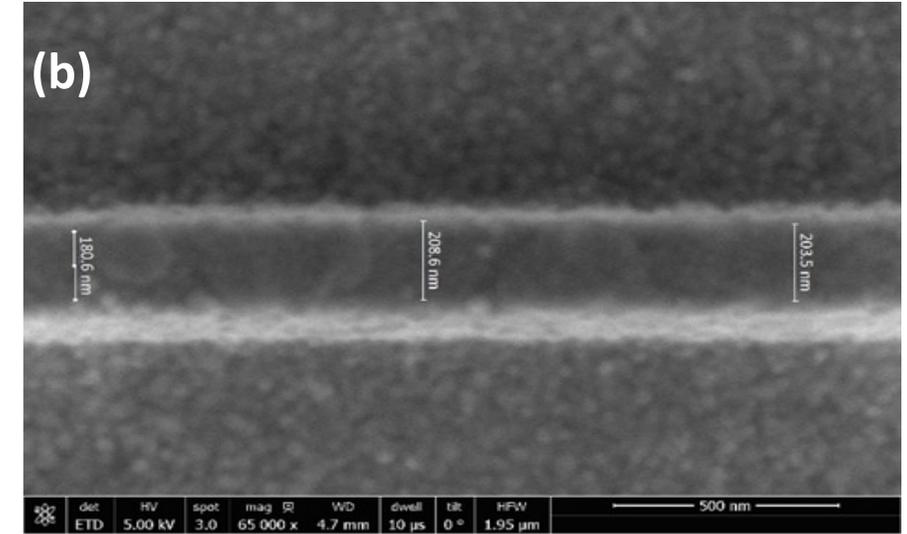
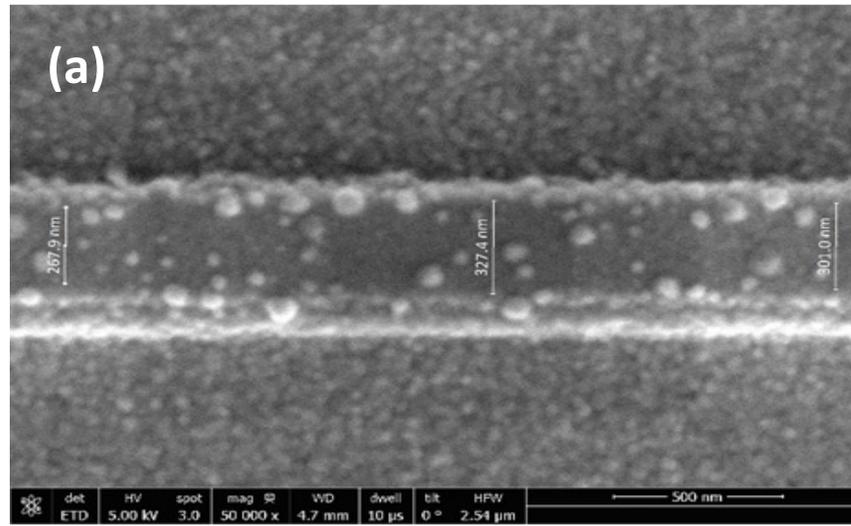
ma-N 2403 (negative) resist



PMMA (positive) resist

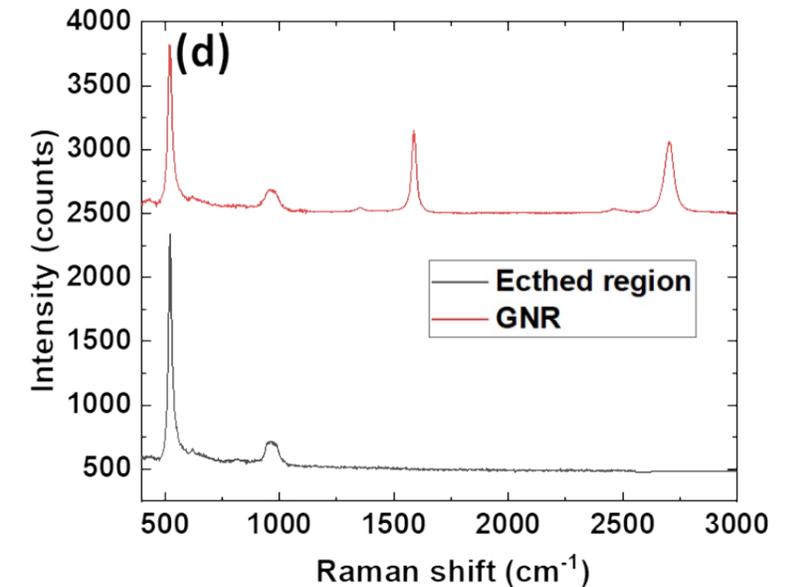
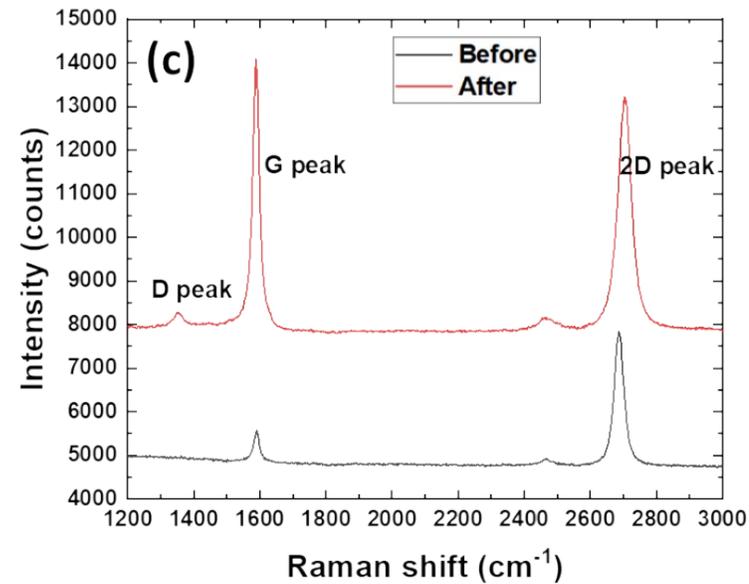
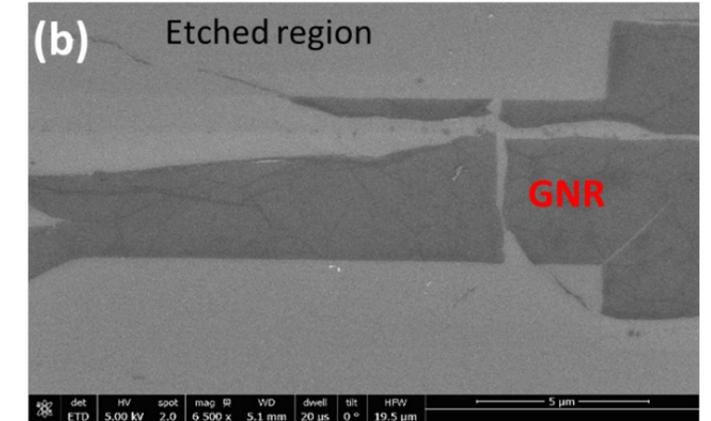
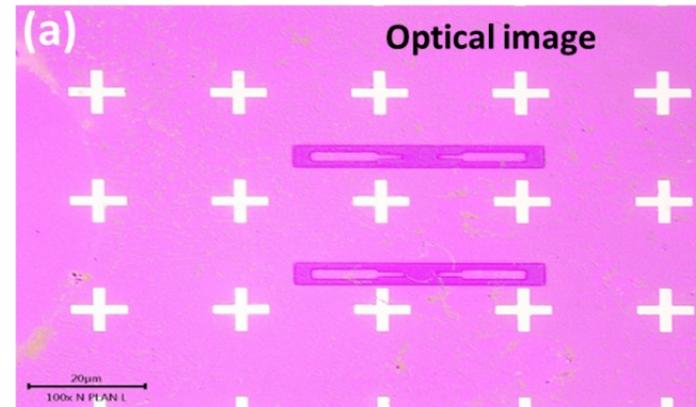
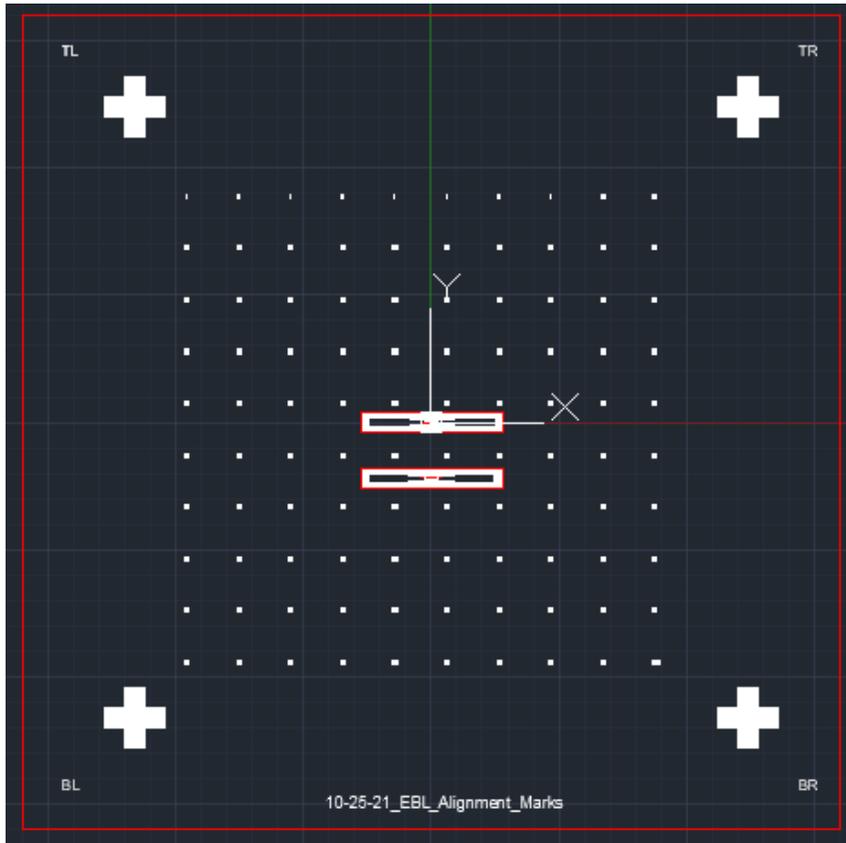


# SEM images: Electron beam lithography (EBL) patterning of graphene into GNRs



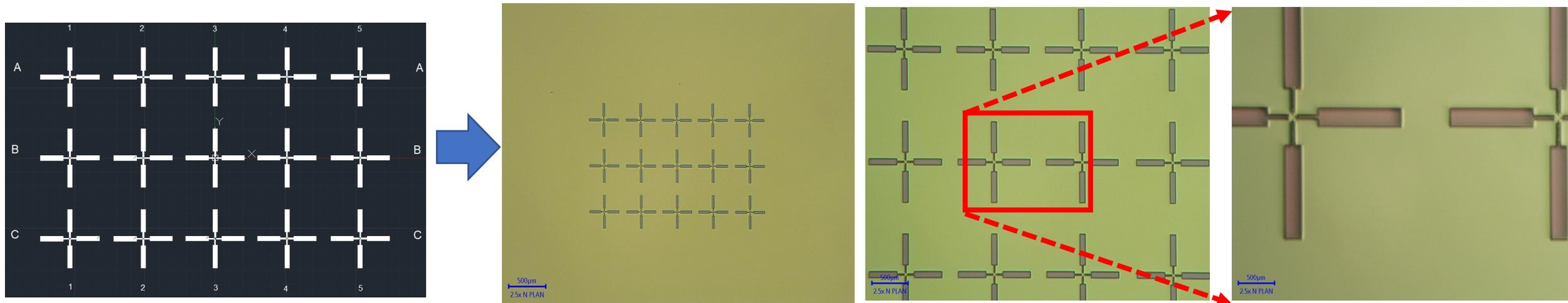
ma-N 2403  
(negative) resist

# Electron beam lithography (EBL) and RIE patterning of graphene into GNRs: Microscopic and Raman study

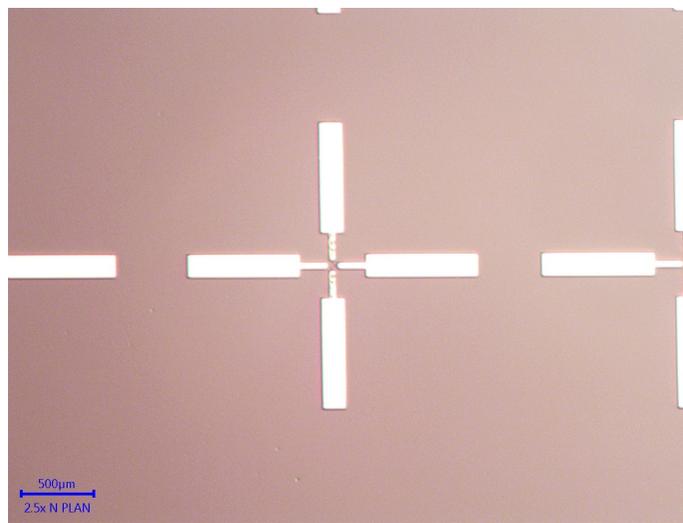


# Electron beam lithography (EBL) patterning for metal electrode deposition

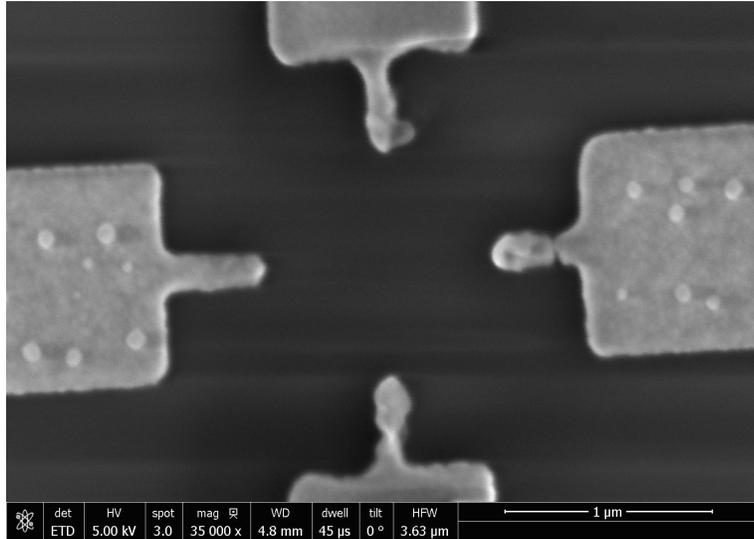
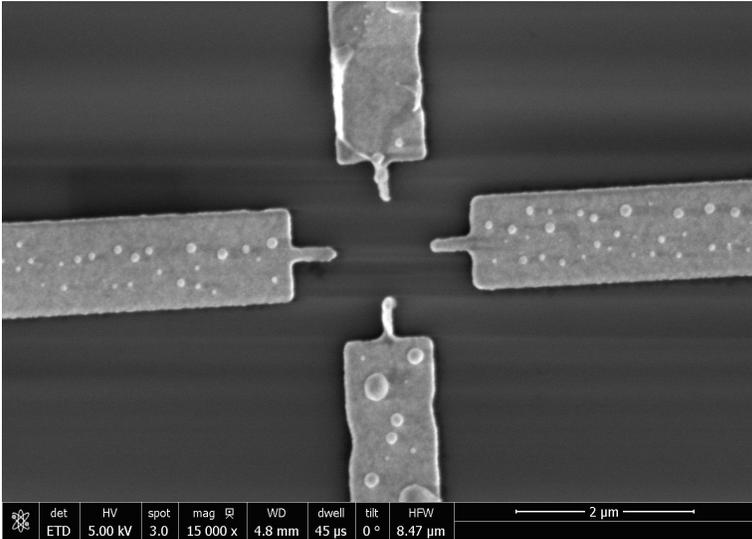
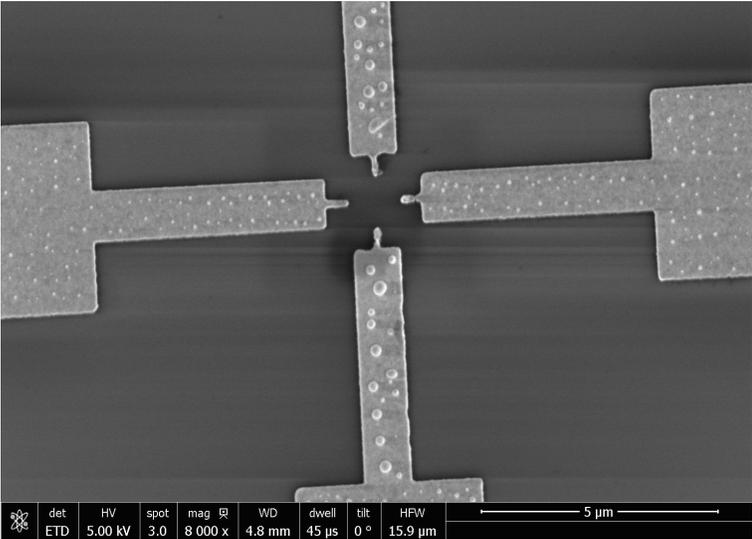
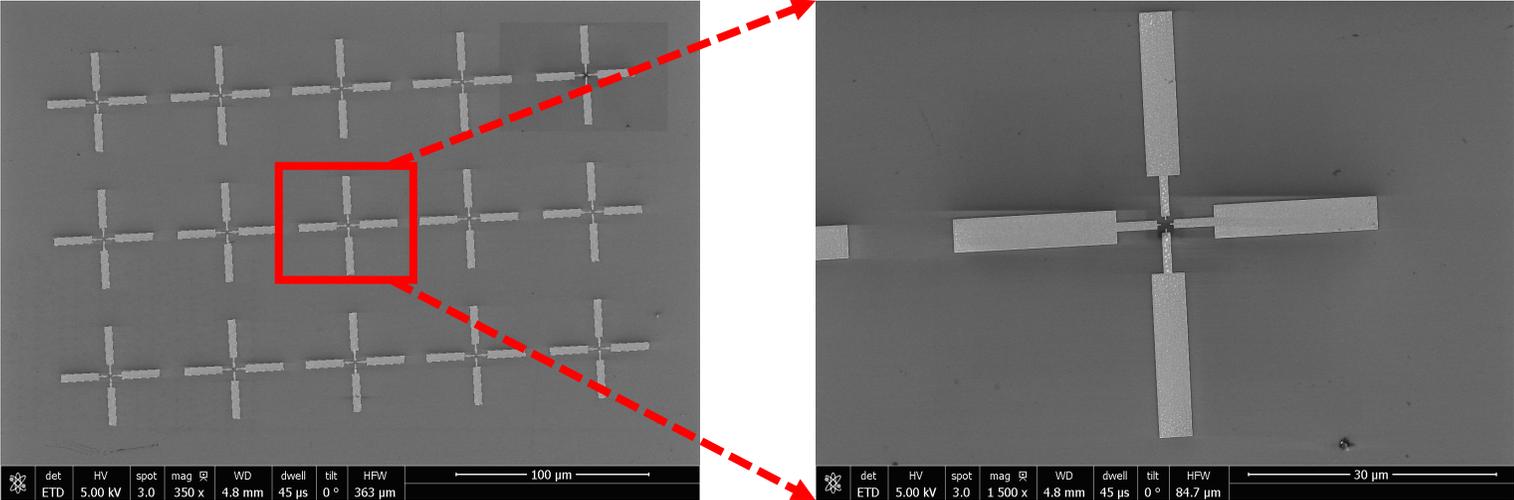
□ After EBL Resist patterning, and development



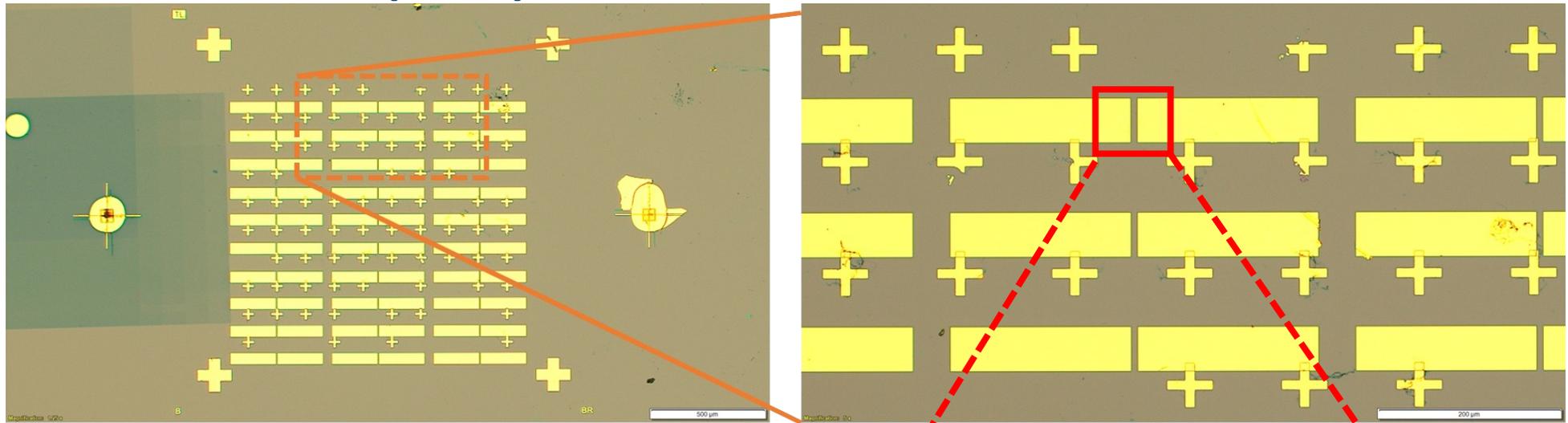
□ After metal (Ti/Au) deposition and lift-off



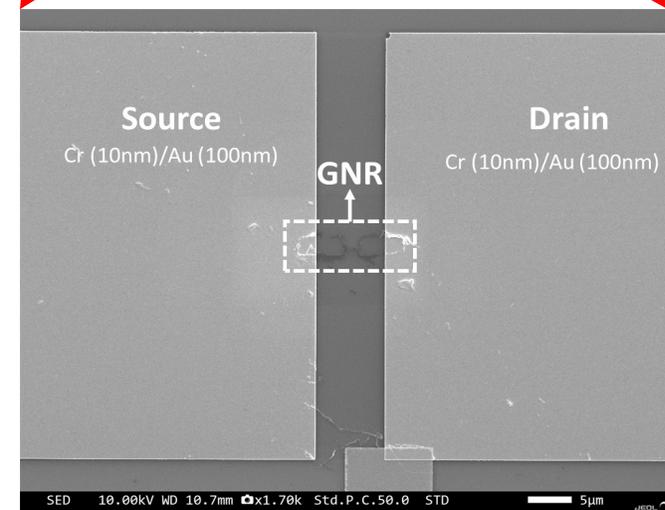
# EBL patterning for metal contact electrodes: SEM images



# Graphene Nanoribbon (GNR) FET device and Electrical Characterization



**Back-gated GNR FET Device with Source and Drain metal electrodes (Cr/Au) on top**

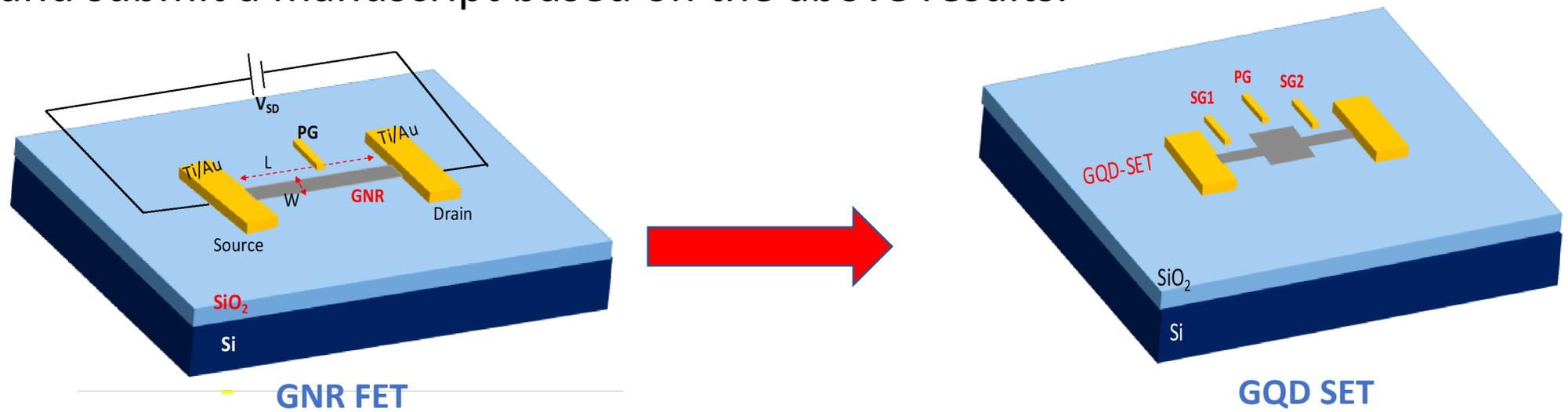


## Project-II: Summary & Action Plan

1. Achieved GNRs with widths  $\sim 60\text{nm}$  by patterning CVD graphene.
2. To conduct STM studies on prepared GNRs and evaluate local density of states to derive correlation between process and edge roughness (CINT/ANL).
3. Continue fabricate FET devices to study the bulk electrical properties of the GNRs.
4. Prepare a manuscript on edge roughness and LDOS for unzipped and EBL prepared GNRs.

## Project-II: Summary & Action Plan

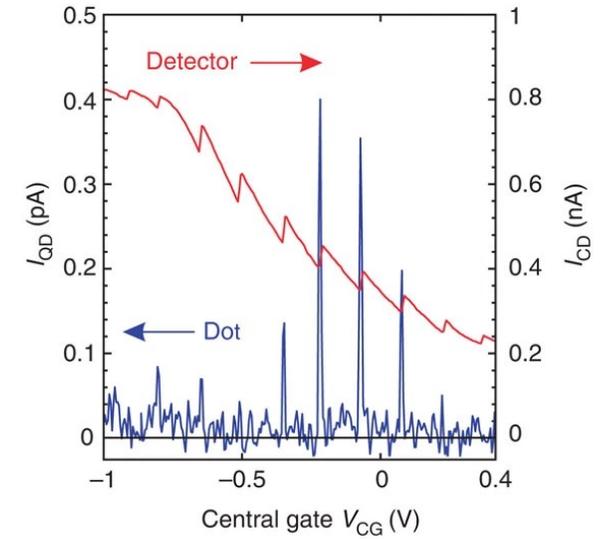
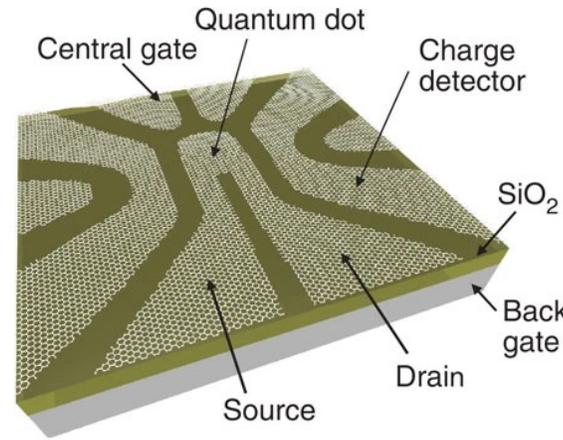
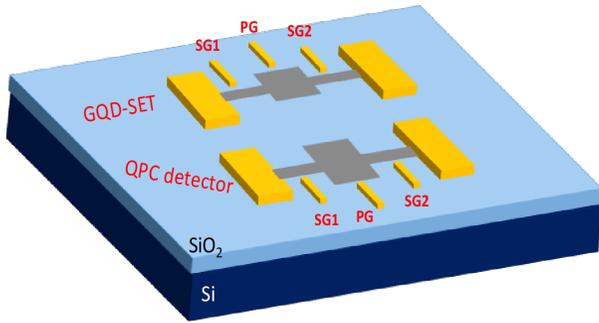
1. Fabrication of single electron transistor (SET) device using unzipped CNT (or GNR) and GNRs prepared using EBL
2. Characterize the electrical and transport properties, analyze and compare the obtained results with traditional CNT, graphene-based SET devices.
3. Prepare and submit a manuscript based on the above results.



## FUTURE WORK

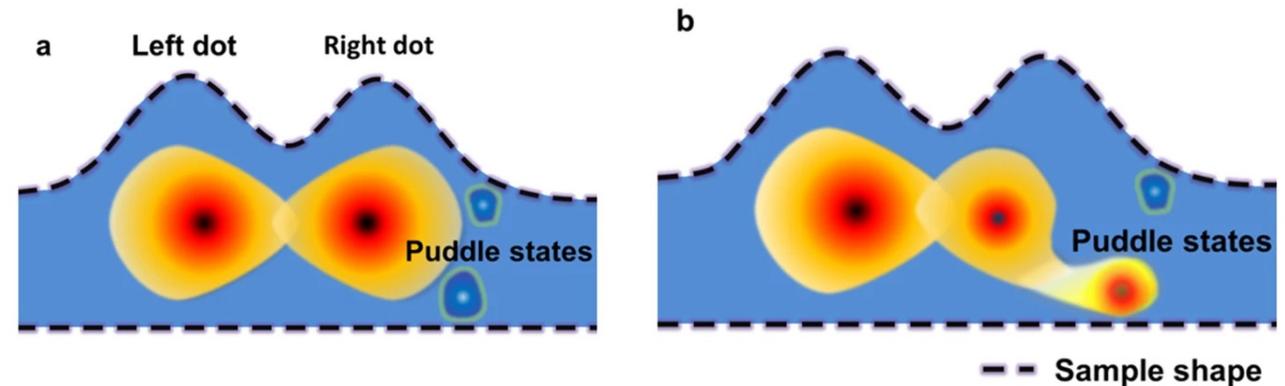
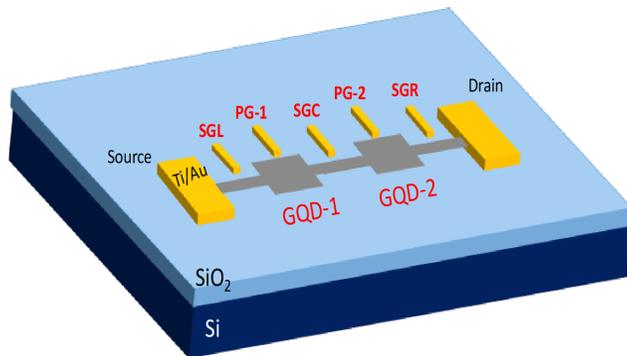


# 1. Characterization of SET using QPC



Nature communications volume 4, 1753 (2013)

# 2. Characterization of Double Quantum Dots



<https://www.nature.com/articles/srep03175#Fig5>

# Publications

## Exclusively from the project

1. “Platinum-like Hydrogen Evolution Reaction Onset for GNR/MoS<sub>2</sub> Heterostructure through curvature-dependent Electron Density Modulation and Enhanced Interfacial Charge Transfer”, Aruna N. Nair, Mohamed F Sanad, Venkata S.N. Chava, and Sreeprasad T. Sreenivasan, (Submitted).

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1. M. F. Sanad, H. M. Franklin, B. A. Ali, A. R. P. Santiago, A. N. Nair, Venkata S.N. Chava, Olivia Fernandez-Delgado, Nageh K. Allam, Steven Stevenson, Sreeprasad T. Sreenivasan, Luis Echegoyen, “Cylindrical C<sub>96</sub> Fullertubes: A Highly Active Metal Free O<sub>2</sub>-Reduction Electrocatalyst”. *Angewandte Chemie* (2022).
2. Mohamed F Sanad, Venkata S. N. Chava, Ahmed Shalan, Lissette G. Enriquez, Ting Zheng, Srikanth Pilla, Sreeprasad Sreenivasan, “Engineering of Electron Affinity and Interfacial Charge Transfer of Graphene for Self-powered Non-enzymatic Biosensor Applications”, *ACS Applied Materials & Interfaces* 13 (34), 40731-40741.
3. Venkata S.N. Chava, P.S. Chandrasekhar, Ashley Gomez, Luis Echegoyen and Sreeprasad T. Sreenivasan, “Efficient inverted planar perovskite solar cells with enhanced open circuit voltage and fill factor using Ti<sub>3</sub>C<sub>2</sub>T<sub>x</sub> MXene doping of PCBM electron transporting layer”, *ACS Applied Energy Materials* 4 (11), 12137–12148.
4. Graphene Nanoribbon-Fullerene (GNR-C<sub>60</sub>) Heterostructure for Nitrogen Reduction Reaction, Aruna N. Nair and Sreeprasad T. Sreenivasan, 240<sup>th</sup> Electrochemical Society (ECS) Meeting, Oct 10-14, 2021

# Thank You!

